

FORM PTO-1449 (REV.7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 500188.02	APPLICATION NO. 09/616,794
O P E INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		APPLICANT(S) Jason B. Elledge	
NOV 24 2003		FILING DATE July 14, 2000	GROUP ART UNIT 3723

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Sevin	AA	6,254,459 B1	07/03/01	Bajaj et al.	451	41	
	AB	6,454,630 B1	09/24/02	Tolles	451	6	
	AC	6,458,014 B1	10/01/02	Ihsikawa et al.	451	6	
	AD	6,607,422 B1	08/19/03	Swedek et al.	451	6	
	AE	6,612,901 B1	09/02/03	Agarwal	451	6	
SLM	AF	20010044261 A1	11/22/01	Elledge	451	41	
	AG						RECEIVED
	AH						DEC 02 2003
	AI						TECHNOLOGY CENTER R3700
	AJ						

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	AK						
	AL						
	AM						
	AN						
	AO						

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AP	
AQ	
AR	

EXAMINER

DATE CONSIDERED

*Shawna NeDerve**2/17/05*

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).

FORM PTO-1449 (REV.7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 500188.02	APPLICATION NO. 09/616,794
INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i>		APPLICANT(S) Jason B. Elledge			
		FILING DATE July 14, 2000	GROUP ART UNIT 3723		

JUN 21 2004

U.S. PATENT DOCUMENTS						
EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SLM	AA 6,426,232	07/30/02	Litvak	438	8	
	AB 6,323,046	11/27/01	Agarwal	438	8	
	AC 6,285,035	09/04/01	Taravade	250	559.22	
	AD 6,241,847	06/05/01	Allman et al.	438	8	
	AE 6,121,147	09/19/00	Daniel et al.	438	692	
	AF 6,074,517	06/13/00	Taravade	156	345.13	
	AG 5,948,203	09/07/99	Wang	156	345.03	
	AH 5,872,633	02/16/99	Holzapfel et al.	356	630	
	AI 5,851,135	12/22/98	Sandhu et al.	451	5	
	AJ 5,834,375	11/10/98	Chen	438	692	
	AK 5,730,642	03/24/98	Sandhu et al.	451	6	
	AL 5,700,180	12/23/97	Sandhu et al.	451	5	
	AM 5,667,424	09/16/97	Pan	451	6	
	AN 5,648,847	07/15/97	Ebbing	356	150	
	AO 5,643,050	07/01/97	Chen	451	10	
	AP 5,439,551	08/08/95	Meikle et al.	438	5	
	AQ 5,433,651	07/18/95	Lustig et al.	451	6	
	AR 5,413,941	05/09/95	Koos et al.	438	16	
	AS 5,337,144	08/09/94	Strul et al.	356	357	
SLM	AT					

OTHER PRIOR ART *(Including Author, Title, Date, Pertinent Pages, Etc.)*

SLM	AU	Erkanat, Judy, "Applied Materials' Mirra chemical mechanical polishing system," <i>Electronic News</i> 41 (2094): p.1, 1991
SLM	AV	Applied Materials, "Dielectric Deposition," http://www.appliedmaterials.com/products/pdd.html , printed 3/2/99

EXAMINER	DATE CONSIDERED
<i>Shantee Medava</i>	<i>2/17/03</i>
* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).	